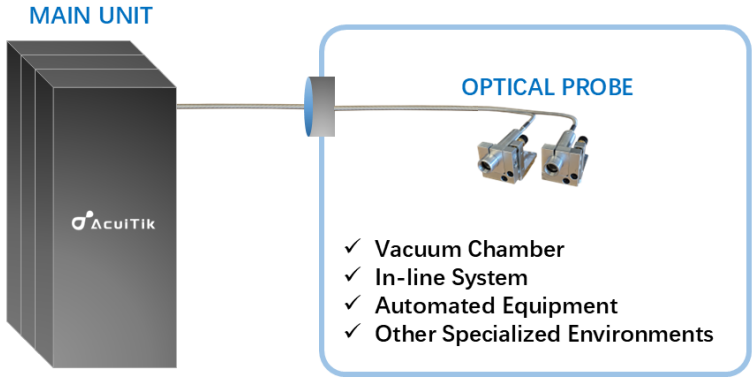
Film Thickness Measurement System NanoSense

NS-OEM series (Film thickness Kit)



The NS-OEM is based on the NS-20 film thickness measurement equipment. Its optical probe is designed to be compact, allowing for installation in various conditions. To ensure accurate measurements, the optical probe must be positioned perpendicular to the sample surface. We recommend using our adjustment tool to fine-tune the installation angle. The optical probe is connected to the main unit via an optical fiber, which offers flexible length options to accommodate different setups.

- Wavelength Range: 190–1000 nm or 350–1100 nm.

- The optical probe is designed for integration into automated equipment, in-line systems, vacuum chambers, in-situ growth chambers, and other specialized environments to meet diverse application requirements.

AcuiTik

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NS-OEM Series Specifications

Model Type	NS-OEM
Wavelength Range	UV: 190 nm - 1100 nm STANDARD: 350-1050 nm HR980: 950 – 1100 nm
Thickness Measurement Range[1]	1 nm – 1 mm
Accuracy[2]	2 nm or 0.2%
Precision[3]	0.02 nm
Spot Size	200 nm ~ 2 mm, standard is 1.5 mm
Measurement Speed[4]	< 1s （Single Measurement）
Light Source	UV: Halogen + Deuterium Lamp STANDARD: Halogen Lamp HR980: SLED
Main Unit – Optical Probe Connection	Optical fiber
Fiber Length	1.3 meters (Standard), flexible length options to accommodate different setups, up limit is 20 m.
Optical Probe Size	Diameter: 19 mm, length: 86 mm
Power Supply	90-264VAC, 47-63Hz, 1.4A/115VAC 1A/230VAC

1.Depends on the specific material, and the selected wavelength range.
2.Si/SiO2 (500~1000nm) standard film sample.
3.Calculate the 1x standard deviation of 100 measurements of a 500nm SiO2 standard wafer, and take the average of the 1x standard deviations over 20 valid measurement days.
4.Depend on specific recipe.